

**ADEX-SUOX Average Best Processing Conditions
Calculated From Data on Silicon**

FTh, μm	Dose, mJ/cm^2	Devl t, min	Trench, μm	Holes, μm	Posts, μm
25	700	15	6	13	5
50	792	21	7	14	6
100	975	34	9	15	8
150	1158	47	10	17	10
200	1341	60	12	19	12
250	1524	73	14	20	14
300	1707	86	15	22	15
350	1890	99	17	24	17
500	2439	138	22	29	23

* Adjust dose for reflectivity of substrate, Cu = 2X